IMPROVED FUSE PROCESS USING LASER EXPOSURE OF FUSE RESIST

Abstract

A method for isolating defective circuits on an integrated circuit having a base layer (32) with an oxide insulating layer (34) covering a conductor connection (30) to the defective circuit, all covered with a photo sensitive polymer (36), includes selectively exposing the polymer (36) covering the conductor to light, dissolving the exposed polymer (36) with a predetermined solution to wash away the exposed polymer, dissolving the oxide insulating layer (34) covering the conductor (30) and with a second predetermined chemical reaction, removing the conduction path to the defective circuit.

Figure 3A-3E